Ĺ	Hits	Search Text	DB	Time stamp
Number		2012011		Time Scamp
100	4	(("5686504") or ("6358606") or	USPAT;	2004/06/25
1.01		("6224949") or ("5288827")).PN.	US-PGPUB	13:56
101	78566	semiconductor same wafer	USPAT;	2004/06/25
102	0	///"=696=04") ("63=9606")	US-PGPUB	14:43
102	"	((("5686504") or ("6358606") or ("6224949") or ("5288827")).PN.) and	USPAT; US-PGPUB	2004/06/25
		(semiconductor same wafer)	US-PGPUB	13:57
103	0	semiconductor and ((("5686504") or	USPAT;	2004/06/25
		("6358606") or ("6224949") or	US-PGPUB	13:57
		("5288827")).PN.)		1
104	0	wafer and ((("5686504") or ("6358606") or	USPAT;	2004/06/25
		("6224949") or ("5288827")).PN.)	US-PGPUB	13:58
105	27626	pressure adj sensitive adj adhesive	USPAT;	2004/06/25
100	1,6500		US-PGPUB	14:44
106	16588	photoinitiator photoinitiators	USPAT;	2004/06/25
		photopolymerization adj (initiator initiators)	US-PGPUB	14:44
107	488	(semiconductor same wafer) and (pressure	USPAT;	2004/06/25
	[adj sensitive adj adhesive)	US-PGPUB	13:59
108	87	((semiconductor same wafer) and (pressure	USPAT;	2004/06/25
	[adj sensitive adj adhesive)) and	US-PGPUB	13:59
		(photoinitiator photoinitiators		
		photopolymerization adj (initiator		
109	65.0	initiators))		
109	652	molar adj (adbsorptivity absorption)	USPAT;	2004/06/25
110	16	(photoinitiator photoinitiators	US-PGPUB USPAT;	14:00 2004/06/25
	10	photopolymerization adj (initiator	US-PGPUB	14:00
		initiators)) same (molar adj	OB TOLOD	11.00
		(adbsorptivity absorption))		
111	0	((photoinitiator photoinitiators	USPAT;	2004/06/25
		photopolymerization adj (initiator	US-PGPUB	14:00
		initiators)) same (molar adj		
		(adbsorptivity absorption))) and		
		<pre>((semiconductor same wafer) and (pressure adj sensitive adj adhesive))</pre>	:	
112	82	maximum adj (adbsorptivity absorption)	USPAT;	2004/06/25
	0.2	same (photoinitiator photoinitiators	US-PGPUB	14:01
		photopolymerization adj (initiator	00 10102	
		initiators))		
113	2	(maximum adj (adbsorptivity absorption)	USPAT;	2004/06/25
ļ		same (photoinitiator photoinitiators	US-PGPUB	14:01
		photopolymerization adj (initiator		
		initiators))) and ((semiconductor same		
		<pre>wafer) and (pressure adj sensitive adj adhesive))</pre>		
114	2	(maximum adj (adbsorptivity absorption)	USPAT;	2004/06/25
	_	same (photoinitiator photoinitiators	US-PGPUB	14:02
		photopolymerization adj (initiator		
		initiators))) and (semiconductor same		
115	_	wafer)		
115	0	((photoinitiator photoinitiators	USPAT;	2004/06/25
		photopolymerization adj (initiator initiators)) same (molar adj	US-PGPUB	14:02
		(adbsorptivity absorption))) and		
		(semiconductor same wafer)		
116	0	(((semiconductor same wafer) and	USPAT;	2004/06/25
		(pressure adj sensitive adj adhesive))	US-PGPUB	14:02
	İ	and (photoinitiator photoinitiators		
l		photopolymerization adj (initiator		
		initiators))) and (molar adj		
		(adbsorptivity absorption))		

117	2	(((===================================	USPAT;	2004/06/25	
		(pressure adj sensitive adj adhesive))	US-PGPUB	14:03	
		and (photoinitiator photoinitiators			
		photopolymerization adj (initiator	-		
	1	initiators))) and (maximum adj		İ	ı
	1	(adbsorptivity absorption) same (photoinitiator photoinitiators			
	1	photopolymerization adj (initiator		1	
1		initiators)))			ı
118	9911		USPAT;	2004/06/25	
			US-PGPUB	14:04	١
119	202	morpholinophenyl same photoinitiator	USPAT;	2004/06/25	
			US-PGPUB	14:04	-
120	301	morpholino same photoinitiator	USPAT;	2004/06/25	ı
100			US-PGPUB	14:04	- [
121	25		USPAT;	2004/06/25	- 1
		adj sensitive adj adhesive)) and	US-PGPUB	14:04	
122	2	(\$phosphine adj oxide) ((semiconductor same wafer) and (pressure	IICDAM.	2004/06/05	-
1-2-2	-	adj sensitive adj adhesive)) and	USPAT; US-PGPUB	2004/06/25	
		(morpholinophenyl same photoinitiator)	03-PGPUB	14:04	1
123	1		USPAT;	2004/06/25	
		adj sensitive adj adhesive)) and	US-PGPUB	14:04	
1		(morpholino same photoinitiator)			
124	50149		USPAT;	2004/06/25	- 1
		wavelength) (second adj wavelength and	US-PGPUB	14:05	-
-	1	first adj wavelength) (second adj			ı
125	25	wavelength same first adj wavelength) (((semiconductor same wafer) and			i
123	23	((tsemiconductor same water) and (pressure adj sensitive adj adhesive))	USPAT; US-PGPUB	2004/06/25	
	1	and (\$phosphine adj oxide))	US-PGPUB	14:05	-
		(((semiconductor same wafer) and	ı		
		(pressure adj sensitive adj adhesive))			1
		and (morpholinophenyl same			-
		photoinitiator)) (((semiconductor same			1
	İ	wafer) and (pressure adj sensitive adj			
		adhesive)) and (morpholino same photoinitiator))			ı
126	89371	semiconductor same wafer	EPO; JPO;	2004/06/25	
		Some walci	DERWENT	2004/06/25	-
127	22055	pressure adj sensitive adj adhesive	EPO; JPO;	2004/06/25	1
			DERWENT	14:44	ı
128	13637	photoinitiator photoinitiators	EPO; JPO;	2004/06/25	
		photopolymerization adj (initiator	DERWENT	14:44	1
129		initiators)			ı
129	0	(clearcoat same (automobile automotive vehicle)) and ((topcoat topcoats) same	EPO; JPO;	2004/06/25	
		(automobile automotive vehicle)) and	DERWENT	14:45	1
		((clearcoat same (automobile automotive			ı
		vehicle)) and ((sag drip run) near			
		resistance))			
130	0	((topcoat topcoats) same (automobile	EPO; JPO;	2004/06/25	ı
		automotive vehicle)) and ((clearcoat same	DERWENT	14:45	
]	(automobile automotive vehicle)) and			
131		<pre>((sag drip run) near resistance)) ((topcoat topcoats) same (automobile</pre>	EPO; JPO;	2004/06/25	
10.	ľ	automotive vehicle)) and (clearcoat same	DERWENT	2004/06/25 14:45	1
	, !	(automobile automotive vehicle))	TINGMUT	14:42	
132	0	((topcoat topcoats) same (automobile	EPO; JPO;	2004/06/25	
		automotive vehicle)) and wafer	DERWENT	14:45	
133	5237	adhesive and wafer	EPO; JPO;	2004/06/25	
134	19	/gomi gonduston seems of	DERWENT	14:45	
124	19	(semiconductor same wafer) and (pressure adj sensitive adj adhesive) and	EPO; JPO;	2004/06/25	
		(photoinitiator photoinitiators	DERWENT	14:53	
		photopolymerization adj (initiator			
		initiators))			
135	1	("5384007").PN.	USPAT;	2004/06/25	
			US-PGPUB	14:54	